

ABSTRACT OF THE DISCLOSURE

An object of the present invention to provide an apparatus for processing a substrate through successive
5 steps including spin-drying the substrate with a single processing facility while preventing the substrate from being contaminated by a substrate processing liquid, etc. An apparatus for processing a substrate of the present invention, including a substrate holder for holding and
10 rotating a substrate, a scattering prevention cup for circumferentially surrounding the substrate held by the substrate holder to prevent a substrate processing liquid supplied to the substrate from being scattered around, and a scattering prevention cup cleaner for cleaning an inner wall
15 surface of the scattering prevention cup.